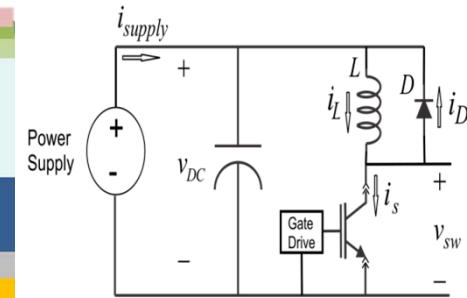
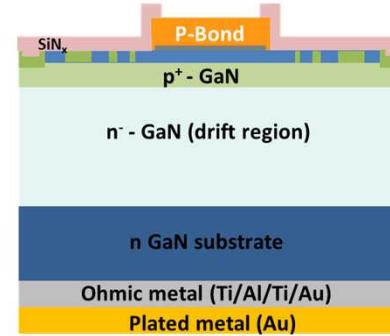
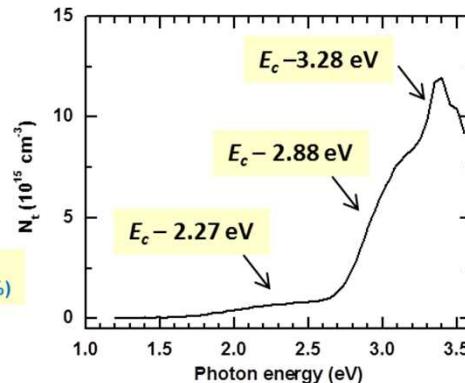
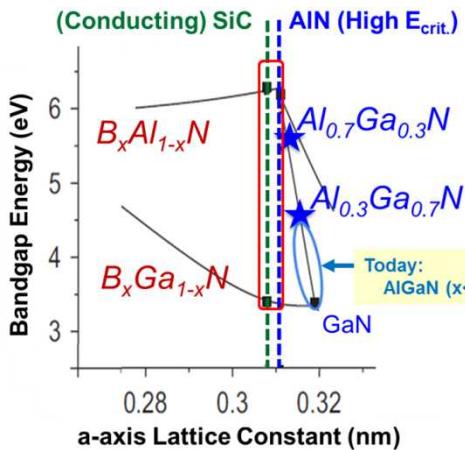


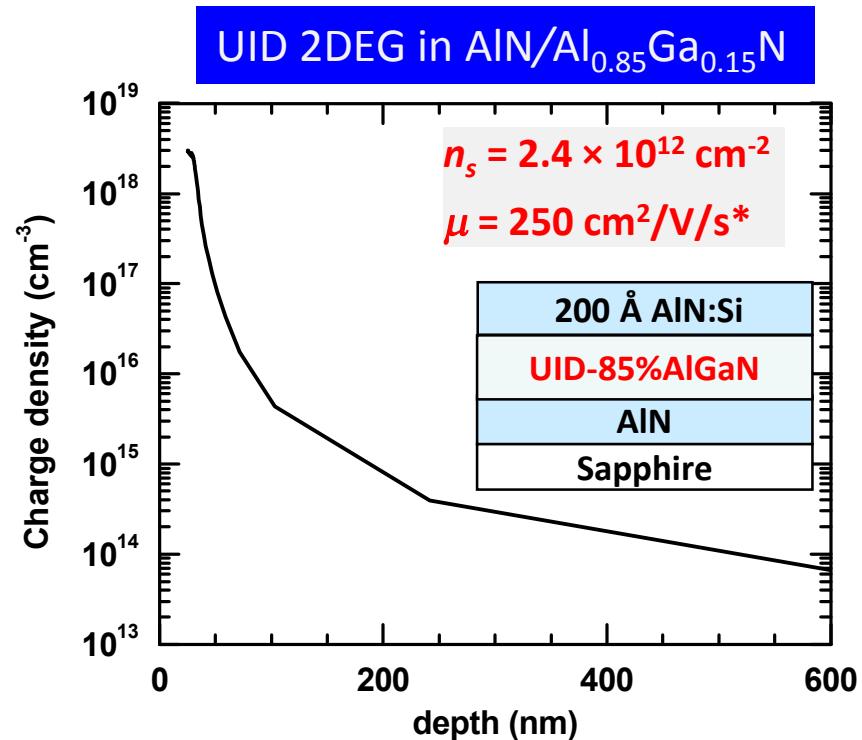
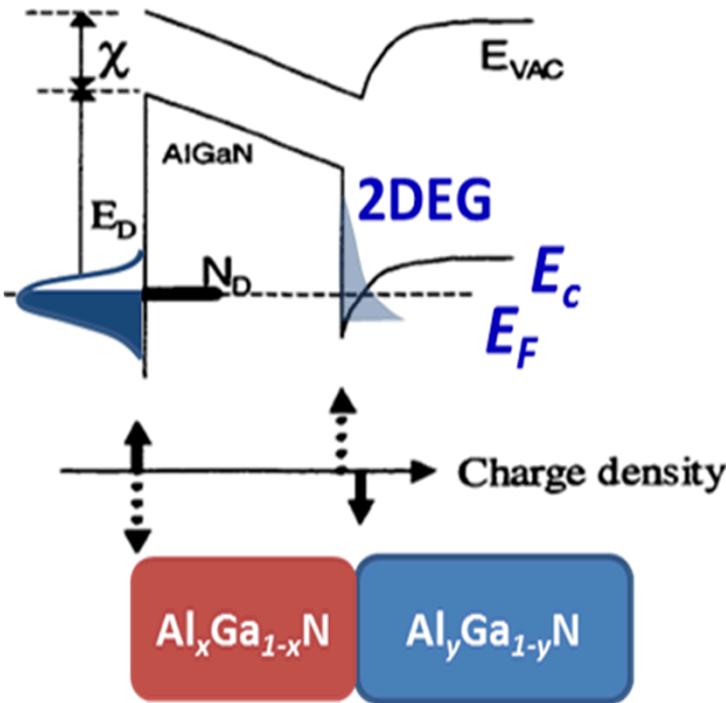
Exceptional service in the national interest



Advanced UWBG heterostructure characterization

A. M. Armstrong, T. Ohta

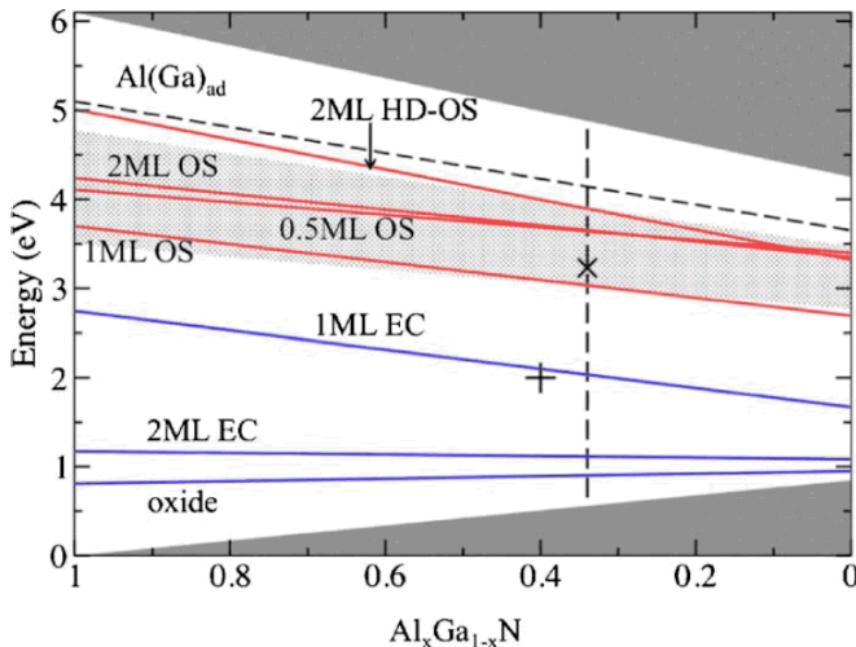
Understand AlGaN spontaneous two-dimensional electron gas formation



- First demonstration of two-dimensional electron gas (2DEG) in unintentionally doped (UID) Al_yGa_{1-y}N/Al_xGa_{1-x}N HEMT $y > x > 0.6$
- Apply advanced surface science to AlN/AlGaN to definitively determine physical source of 2DEG

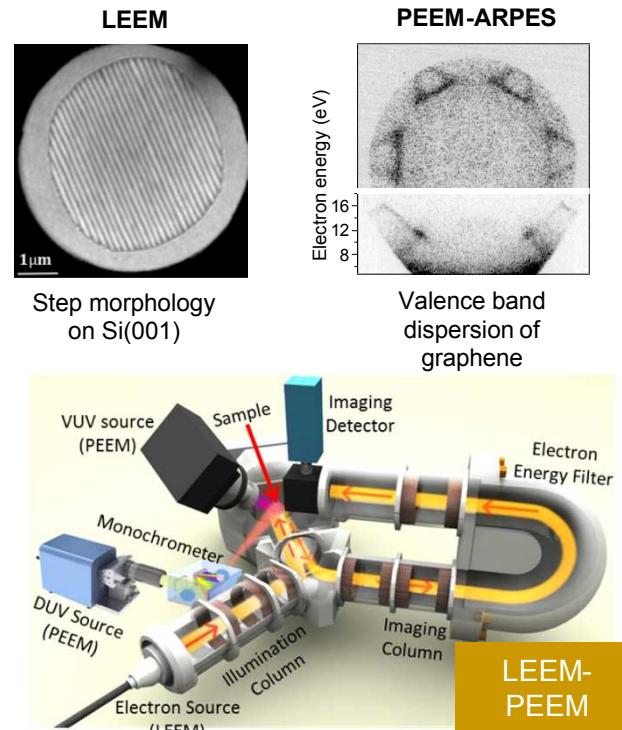
Understand AlGaN spontaneous two-dimensional electron gas formation

Understand and control electronic properties of UWBG Al(Ga)N surface



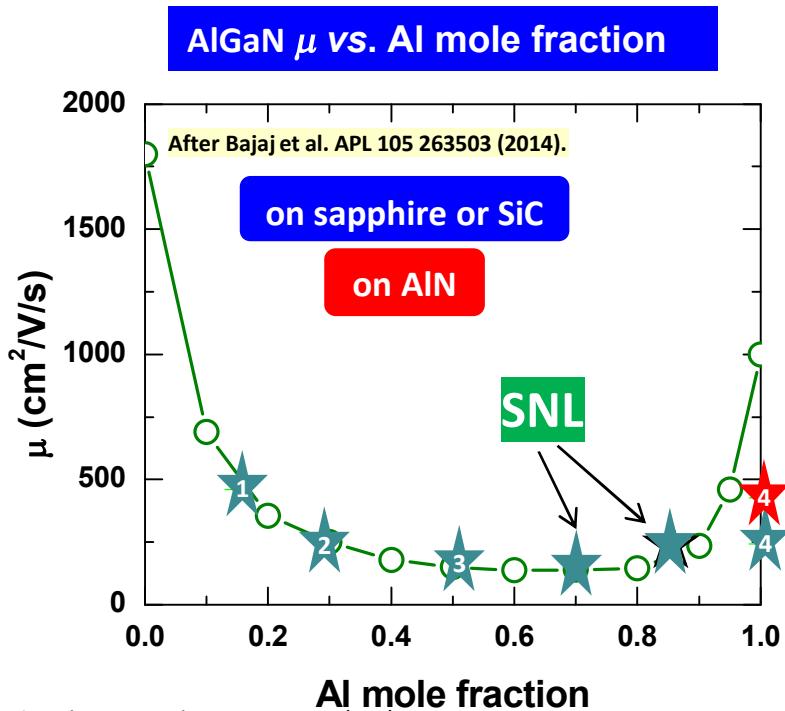
1. Miao et al. J. Appl. Phys. 107 123713 (2010).

LEEM-PEEM surface characterization

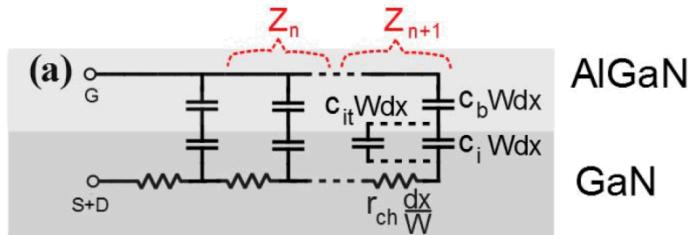


- Use LEEM-PEEM to correlate Al(Ga)N surface structure, chemistry, & electronic properties at sub- μm length scale
- Study as a function of growth conditions, oxidation, and post-growth thermal treatment

Characterize UWBG AlGaN heterostructures with AWE/Bristol



AWE/Bristol $C-V-f$ model for heterostructures



$$Z_{n+1} = \left(j\omega c W \Delta x + \frac{1}{Z_n} \right)^{-1} + r_{ch} \frac{\Delta x}{W}$$

$$r_{ch} = \frac{1}{\mu_0 n i q}$$

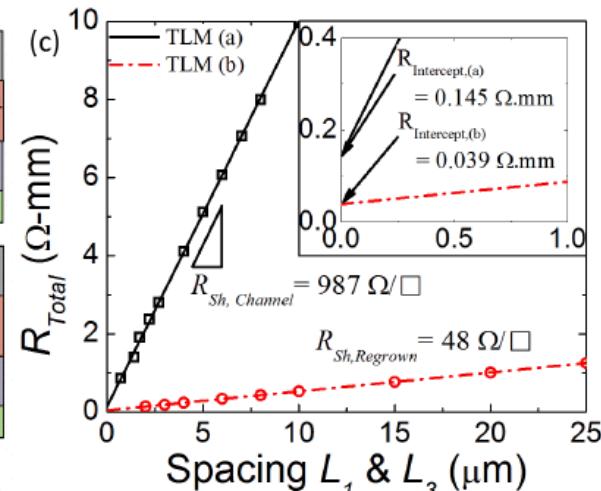
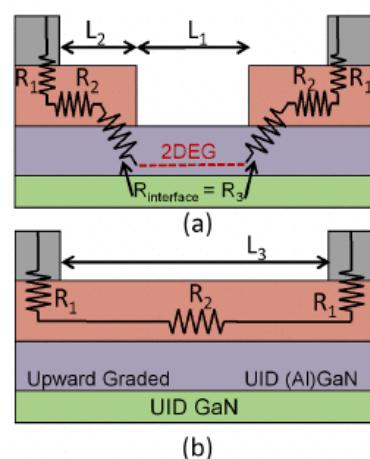
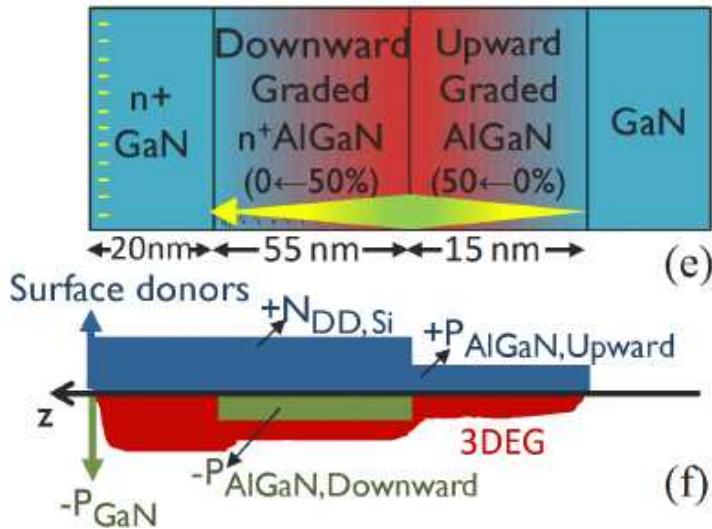
Waller *et al.*, IEEE TED 2464 62 2015

1. Nanjo *et al.* IEEE Trans. Electron Dev. 60 1046 (2013).
2. Hashimoto *et al.* SEI Tech. Rev. 71 83 (2010).
3. Hashimoto *et al.* PSS A 209 501 (2012).
4. Taniyusa *et al.* APL 89 182112 (2006).

- Measuring μ is critical to establishing AlGaN HEMTs
 - Typically requires ohmic contacts
- SNL will work with AWE/Bristol to extract AlGaN heterostructure interface states and channel mobility from Schottky diodes

Reverse graded contacts with Ohio State

Potential path for re-growth free ohmic contacts



- Ohio State (Prof. Rajan) has demonstrated low resistance ohmic contacts to UWBG AlGaN
- SNL has provided graded AlGaN samples for contact re-growth by OSU
- Promising approach for a MESFET-type device